

EXAMINER'S AMENDMENT

An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Ryan Smith on 05/19/11.

The application has been amended as follows:

In claim 5, line 10, after "made of aluminum or an aluminum alloy" insert -- including an aluminum fluoride passivation film thereon--.

In claim 5, line 27, after "a bottom surface of the dielectric plate" insert --and the gas supply member--.

In claim 5, line 28, after "species generated from the cleaning gas" insert -- wherein during the cleaning at least a portion of the aluminum fluoride passivation film is removed from a surface of the gas supply member made of aluminum or aluminum alloy, thereby exposing a surface of the aluminum or aluminum alloy--.

In claim 5, line 31, after "to activate the gaseous mixture, oxidizing the" insert -- exposed aluminum or aluminum alloy--.

Claim 7 is canceled.

Allowable Subject Matter

The following is an examiner's statement of reasons for allowance:

The instant invention is distinguished over the prior art of record by a method for the metallization of a plastic tank by physical vapor deposition comprising the steps of: a plasma processing method for forming a fluorine containing carbon film on a surface of a substrate using a plasma processing apparatus, particularly comprising a gas supply member made of aluminum or an aluminum alloy including an aluminum fluoride passivation film thereon, where after film deposition a cleaning gas containing oxygen and hydrogen is supplied to the gas supply member that at least a portion of the aluminum fluoride passivation film is removed from the surface of the gas supply member made of aluminum or aluminum alloy, thereby exposing a surface of the aluminum or aluminum alloy and further supplying an oxygen containing gas to form an oxide film on the exposed aluminum or aluminum alloy surface of the gas supply member.

Barnes [US 20040077511] teaches a method of cleaning a plasma reactor, wherein hydrogen and oxygen containing gas is supplied to the reactor and a subsequent oxygen gas is supplied to the reactor for cleaning [0032]. However, Barnes fails to teach a gas supply member made of aluminum or an aluminum alloy including an aluminum fluoride passivation film thereon, wherein the oxygen and hydrogen containing gas is supplied to the gas supply member that at least a portion of the aluminum fluoride passivation film is removed from the surface of the gas supply member made of aluminum or aluminum alloy, thereby exposing a surface of the aluminum or aluminum alloy and further supplying an oxygen containing gas to form an

oxide film on the exposed aluminum or aluminum alloy surface of the gas supply member.

Sandhu [US 6162499] teaches a method of inhibiting deposit on the reactor walls, where oxygen gas is supplied to the surface of an aluminum containing wall to form aluminum oxide layer thereon [col 3, ln 40-58]. However, Sandu fails to teach a gas supply member made of aluminum or an aluminum alloy including an aluminum fluoride passivation film thereon, wherein the oxygen and hydrogen containing gas is supplied to the gas supply member that at least a portion of the aluminum fluoride passivation film is removed from the surface of the gas supply member made of aluminum or aluminum alloy, thereby exposing a surface of the aluminum or aluminum alloy.

Acknowledgement of Applicant's Amendments

The rejection of the claims under 35 U.S.C. 103 is withdrawn due to Examiner's amendments; hence, subject matter is due for allowance.

Conclusion

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to MANDY C. LOUIE whose telephone number is (571)270-5353. The examiner can normally be reached on Monday to Friday, 7:30AM - 5:00PM EST.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Timothy Meeks can be reached on (571)272-1423. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

/M. C. L./
Examiner, Art Unit 1715

/Timothy H Meeks/
Supervisory Patent Examiner, Art Unit 1715